

AN 121:241716 HCA Full-text  
 TI Electrophotographic liquid developer  
 IN Kato, Eiichi  
 PA Fuji Photo Film Co Ltd, Japan  
 SO Jpn. Kokai Tokkyo Koho, 63 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	JP 06051569	A2	19940225	JP 1992-219554	19920728
	JP 2916560	B2	19990705		
PRAI	JP 1992-219554		19920728		

AB In the title developer containing at least resin particle dispersion in a nonaq. solvent with an elec. resistivity  $\geq 10^9 \Omega\text{cm}$  and a dielec. constant  $\leq 3.5$ , the resin particles are made of a A-B block graft copolymer grain obtained by the steps of: (1) forming a A block made up of (a) a monofunctional monomer, a macromonomer with  $M_w \leq 10,000$  having polymerizable double bond only one end of the backbone chain, a polyfunctional monomer, and a polymer component with a polar moiety; (2) forming an A-B block copolymer, in which a B block contains a polymerizable component and a monofunctional polymerizable double bond at the end of the B block, (3) polymerizing a monomer containing  $C \geq 8$  aliphatic, and (4) further polymerizing the resulting polymer in a dispersion stabilizing resin soluble in the nonaq. solvent.

IC ICM G03G009-13

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other

Reprographic Processes)

ST electrophotog liq developer polymer particle

IT Electrophotographic developers

(resin particles in electrophotog. liquid developer)

IT 112955-45-0P 112955-56-3P 114512-15-1P 138005-06-8DP,  
 carboxy-terminated, ester with glycidyl methacrylate 138115-34-  
 1DP,

Ethylmethacrylate-triphenylmethyl methacrylate block copolymer,  
 hydrolyzed, carboxylated, ester with 2-hydroxyethyl methacrylate  
 138232-67-4DP, Benzyl methacrylatebutyl methacrylate block

copolymer,

hydrolyzed, methylstyrene-terminated 139104-82-8P 139104-86-2P

139104-87-3P 139104-88-4P 139104-90-8P 139104-94-2P 139104-  
 96-4P

139105-01-4P 139105-03-6P 139105-07-0P 139105-08-1P 139105-  
 10-5P

139105-12-7P 139357-83-8DP, hydrolyzed, terminated with Et  
 methacrylate

139598-52-0DP, Acrylic acid-octadecyl methacrylate block copolymer,

hydrolyzed, hydroxy-terminated, ester with 2-isocyanatoethyl methacrylate

139598-53-1P	139598-54-2DP, hydrolyzed	139598-55-3DP, hydrolyzed		
139598-56-4DP, hydrolyzed	139598-57-5DP, hydrolyzed	139598-58-6DP, hydrolyzed	139598-59-7DP, hydrolyzed	139598-60-0DP, hydrolyzed
139598-61-1DP, hydrolyzed	139598-62-2DP, hydrolyzed	139598-63-3DP, hydrolyzed	139598-64-4DP, hydrolyzed	139598-65-5P
139598-66-6P	139598-68-8P	139598-69-9P	139598-70-2P	139598-71-3P
139598-72-4P	139598-73-5P	139598-74-6P	139598-75-7P	139598-76-8P
139598-77-9P	139598-80-4P	139598-81-5P	139598-82-6P	139598-83-7P
139598-85-9P	139687-39-1P	141349-31-7P	141414-91-7P	141415-33-0P
139687-39-1P	141440-78-0P	141759-32-2P	141759-37-7P	141759-91-3P
141440-78-0P	141759-32-2P	141759-37-7P	141759-91-3P	143709-75-5P
143709-75-5P	147045-28-1P	147127-63-7P	147130-24-3P	147130-26-5P
147045-28-1P	147130-28-7P	147130-29-8P	147130-30-1P	147130-31-2P
147130-28-7P	147130-33-4P	147130-35-6P	147130-36-7P	147130-37-8P
147130-33-4P	147130-40-3P	147130-41-4P	147130-42-5P	147130-44-7P
147130-40-3P	147130-47-0P	147130-50-5P	150958-16-0DP, hydrolyzed, terminated	
147130-47-0P	156202-69-6P	156620-35-8P	156620-37-0P	
156202-69-6P	158008-00-5DP, hydrolyzed	158008-02-7P	158348-52-8P	158463-91-3P
158008-00-5DP, hydrolyzed	158463-92-4P	158463-93-5P	158463-94-6P	158463-95-7P
158463-92-4P	158463-97-9P	158463-98-0P	158463-99-1P	158464-00-7P
158463-97-9P	158464-02-9P	158464-03-0P	158464-04-1P	158464-05-2P
158464-02-9P	158464-07-4P	158464-08-5P	158464-10-9DP, hydrolyzed	158464-11-0P
158464-07-4P	158464-12-1P	158464-13-2P	158464-14-3P	158464-15-4P
158464-12-1P	158464-18-7P	158464-19-8DP, hydrolyzed		
158464-18-7P	RL: MOA (Modifier or additive use); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)			
(electrophotog. liquid developer)				
IT	158464-09-6	RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)		

(star copolymer initiator; electrophotog. liquid developer)  
IT 138005-17-1P  
RL: MOA (Modifier or additive use); SPN (Synthetic preparation); TEM  
(Technical or engineered material use); PREP (Preparation); USES  
(Uses)  
(star-branched; electrophotog. liquid developer)

AN 125:202403 HCA Full-text

TI Wax patterns for manufacture of molds to be used in investment casting and

manufacture of precision cast products

IN Nakayama, Shinichi; Nikashiwa, Toshiki

PA Yamanashi Prefecture, Japan; Nippon Catalytic Chem Ind

SO Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	JP 08155586	A2	19960618	JP 1994-305087	19941208
PRAI	JP 1994-305087		19941208		

AB The wax patterns are manufactured from vinyl polymers containing 50-100 weight% repeating unit -CH<sub>3</sub>C(R<sub>1</sub>)(BR<sub>2</sub>)- (R<sub>1</sub> = H or Me, R<sub>2</sub>=C<sub>15</sub>-30 aliphatic hydrocarbon, B=-C(:O)O-, -C(:O)NHCH<sub>2</sub>CH<sub>2</sub>OC(:O)-, -C(:O)NHC(OH)CH<sub>2</sub>OC(:O)-, -C(:O)NHCH<sub>2</sub>CH<sub>2</sub>OC(:O)NHR<sub>3</sub>NHC(:O)O-, R<sub>3</sub>=divalent organic group) and/or repeating unit C(COOR<sub>4</sub>)HC(COOR<sub>5</sub>)H- (R<sub>4</sub>, R<sub>5</sub>= independently H or C<sub>1</sub>-30 aliphatic hydrocarbon, but at least one of R<sub>4</sub> and R<sub>5</sub>=C<sub>15</sub>-30 aliphatic hydrocarbon). Dewaxing in the manufacture of precision cast products is conducted by solvent washing or heating and solvent washing. The productivity and quality of precision cast products are improved.

IC ICM B22C009-04

ICS B22C009-18; C08F018-10; C08F020-18; C08F020-58; C08F020-60; C08F022-12

CC 56-2 (Nonferrous Metals and Alloys)

ST vinyl polymer wax pattern investment casting

IT Waxes and Waxy substances

RL: TEM (Technical or engineered material use); USES (Uses)

(vinyl polymer-based wax patterns for manufacture of molds to be used in

investment casting and manufacture of precision cast products)

IT Casting process

(investment, vinyl polymer-based wax patterns for manufacture of molds to be

used in investment casting and manufacture of precision cast products)

IT 25639-21-8 25986-77-0 181123-73-9 181123-76-2

RL: TEM (Technical or engineered material use); USES (Uses)

(vinyl polymer-based wax patterns for manufacture of molds to be used in

investment casting and manufacture of precision cast products)